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(73) 455 - 6

(72) 1029 1 101 - 404

353 - 1403

108 - 1104

11 - 1 522

(74)

:

(54)

, (a)

ITO(indium tin oxide) , (b)

ITO

, (c) ITO

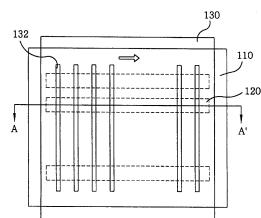
, (d)

, (e)

(c) (d)

,

【도 5c】



2 DBR

3 CCF

4 W - CFF

5a 5c

6a 6d 5c 5c A - A'

<

110 : 120 : ITO

130 : 132 :

140 :

160, 170, 180 : , , ,

가

가 , ,
,
(VFD), (Electroluminescence : EL)

가 (LCD),
(PDP),

가 (Electroluminescence : EL)

CCF (individual pixel type), DBR
, W - CFF

1 (10) (shadow mask) () 가 가
, (R - , G - , B - OELD) (22, 24, 26)
, (22, 24, 26)
가

(10) (ink - jet) 가
가

2 DBR (R), (G) (B)
DBR(Distributed Brag Reflector)(32, 34, 36) (10), DBR(32, 34, 36)
(Broad Band OELD)(42, 44, 46)

3 CCF , 가
(10) ITO , 가
g Film)(52, 54, 56) , (52, 54, 56) (CCF : Color Convertin
66) ,
LCD (CFF : Color Filter Film) (Blue - OELD)(62, 64,
가 가 CCF ,
가 (cross - talk)

4 LCD W - CFF (10)
CFF(72, 74, 76) , (White - OELD)(82, 84, 86)
가

5

5a
0.7mm
)
. , (110) , 가
t1
ITO (120) (+) .
1000 ITO(indium tin oxide)가
ITO (120)

5b (110) 150 - 200 μ m (130)
 가 , 가 1
 (110) ITO(120) μ m (132)
 . (130) t2 (132) , t3 (132)

$$t2^*2 < t3 \quad t2^*5$$

, 5c 6a , ITO (120) (110) (130)
 140) . , (140) AL:Li (150) 3000 , (-)
 6b ITO (120) (140) , (160)
 . (hall injection layer) (142), (hall transfer layer) (144),
 (emission layer) (146), (electron layer) (148)
 (146) , , , (146) , , , (146) , , , (R)
 .
 .
 , ITO (120) (150) (150) (150) (+) (-) , ITO (120)
 iton) , , , ITO (120) 가 (ground state) (exc
 ,
 , (160) , ITO (160) (110) (130) t3
 (160) , 5c (146) (150) (170)
 (160)
 (6c).
 .
 , ITO (110) (130) t3
 (170) , 5c (146) (150) (180),
 170) (160, 170, 180) (130) t3 (200)
 ,
 ,
 , (130) ITO (110) (130) ITO (110)
 (170) , (130) (110) (130) (110)
 , , , ,
 PZT nm
 ,
 ,
 , ITO (120) (150) 가 (146)
 (200) (144) (150) (146)

7

(57)

1.

(a)

ITO(indium tin oxide)

(b)

ITO

(c) ITO

(d)

(e)

(c) (d)

2.

1

(t3)

$t_2 < t_3 < t_5$

, t2

, t3

3.

1 2
injection layer),
(electron layer)

,
(hall transfer layer),

(hall i
(emission layer),

(c)

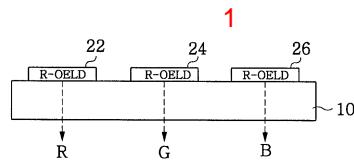
4.

1 , Al:Li

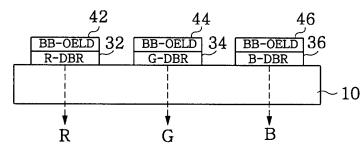
5.

1

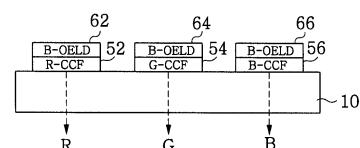
(t3)



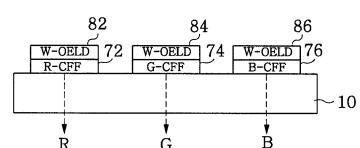
2



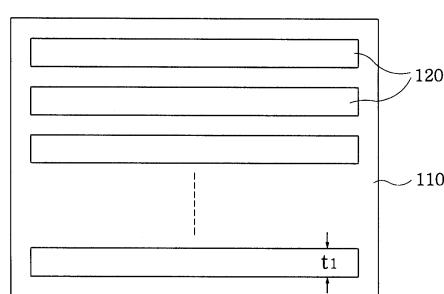
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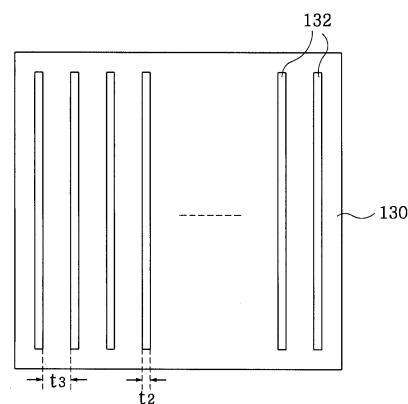
4



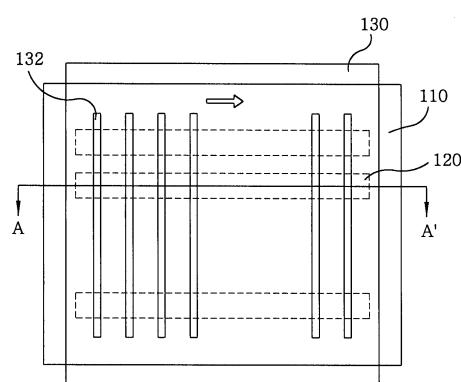
5a



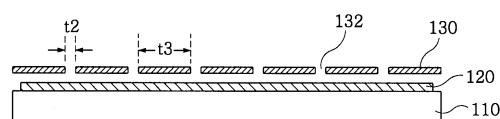
5b



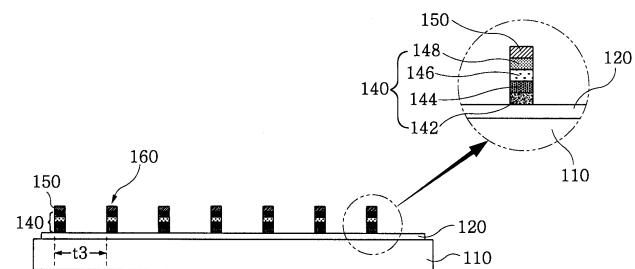
5c



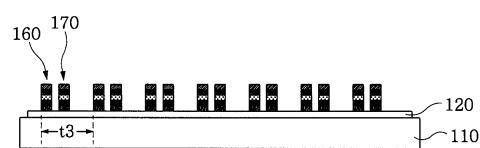
6a



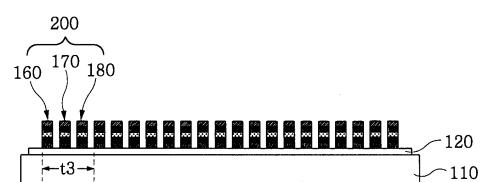
6b



6c



6d



专利名称(译)	使用单分子有机电致发光材料制造全色显示系统的方法		
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外部链接	Espacenet		

摘要(译)

本发明涉及一种方法，用于使用单分子有机电致发光材料制造的全色显示系统中，(a)玻璃图案电极(氧化铟锡)的基板上具有在纵向方向上的矩形形状的ITO屏幕，(b)除去在垂直通过形成多个细长狭缝，从金属板的金属掩模，和(c)具有在ITO电极的玻璃基板上的所述狭缝的金属制得的玻璃基板上的ITO jeongeukwa的方向上的金属部分(D)通过在单分子有机发光材料层上热层压金属混合物形成金属电极，以形成单色有机发光材料(E)在狭缝之间的区域中形成金属掩模，以便与形成的单色有机发光像素区域相邻定位并重复步骤(c)至(d)以形成用于全色显示器的有机电致发光器件。

